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Reaction of Organylchlorosilanes with Dimethyl Sulfoxide in the Presence of Octamethyltrisiloxane

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Abstract—Dichloro(methyl)(vinyl)silane reacts with DMSO in the presence of octamethyltrisiloxane to form cyclooligomethyl(vinyl)siloxanes(MeViSiO)_n (n=3–6). The reaction involves disproportionation of octamethyltrisiloxane into hexamethyldisiloxane and decamethyltetrasiloxane. Along with the latter two products, insertion products of methyl vinyl silanone into both permethyloligosiloxanes were identified. Alkyltrichlorosilanes RSiCl₃ (R = Me, Et) react with DMSO in the presence of octamethyltrisiloxane to form cyclic oligoalkyltrichlorosiloxanes (RClSiO)_m (m = 3–6).

Previously we showed that the reaction of diorganyldichloro- and organyltrichlorosilanes with DMSO in a hexamethyldisiloxane (I) medium is a convenient synthetic route to linear and cyclic organyl-(trimethylsiloxy)siloxanes [1, 2].

The major products of reaction (1) between dichloro(methyl)(vinyl)silane with DMSO in the presence of octamethyltrisiloxane (II) that serves for trapping the intermediate methyl vinyl silanone (III), at 20° C and a 1:1:1 reagent molar ratio are cyclomethyl(vinyl)siloxanes (MeViSiO)_n (IV–VII, n=3-6) in a total yield of 75–80%. Therewith, the yield of insertion products of methyl vinyl silanone into trisiloxane II, namely 1,1,1,3,5,5,7,7,-nonamethyl-3-vinyltetrasiloxane (VIII) and 1,1,1,3,5,7,7,9,9,9-decamethyl-3,5-divinylpentasiloxane (IX), is as low as 3–5%.

$$CH_{3}(CH_{2}=CH)SiCl_{2} + OS(CH_{3})_{2}$$

$$\longrightarrow [CH_{3}(CH_{2}=CH)Si=O] + S(CH_{2}CI)CH_{3}, \quad (1)$$

$$III$$

$$n[MeVinSi=O] \longrightarrow (MeVinSiO)_{n}, \quad (2)$$

$$III \qquad IV-VII$$

$$m[MeVinSi=O] + Me_{3}SiOSiMe_{2}OSiMe_{3}$$

$$II$$

$$\longrightarrow Me_{3}SiOSiMe_{2}O(MeVinSiO)_{m}SiMe_{3}, \quad (3)$$

$$VIII, IX$$

$$n = 3 (IV), 4 (V), 5 (VI), 6 (VII); m = 1 (VIII), 2 (IX).$$

Reaction (2) between MeVinSiCl₂ and DMSO can occur in the absence of trisiloxane II [1], and the yield of compounds IV–VII is slightly higher. At higher concentrations of trisiloxane II in the reaction mixture

(1:1:3 reagent molar ratio), the yield of cyclomethyl-(vinyl)siloxanes **IV**–**VII** is almost the same.

Under the reaction conditions, trisiloxane \mathbf{II} undergoes disproportionation into disiloxane \mathbf{I} and decamethyltetrasiloxane (\mathbf{X}). Neither MeVinSiCl₂ nor DMSO taken separately induce disproportionation of compound \mathbf{II} .

$$\begin{array}{c} 2 \text{Me}_{3} \text{SiOSiMe}_{2} \text{OSiMe}_{3} \\ \hline \textbf{II} \\ \longrightarrow \text{Me}_{3} \text{SiOSiMe}_{3} + \text{Me}_{3} \text{SiOSiMe}_{2} \text{OSiMe}_{2} \text{OSiMe}_{3}. \end{array} \tag{4}$$

Siloxanes **I** and **X** were isolated and characterized by GC–MS, along with insertion products of silanone **III** into disiloxane **I** [1,1,1,3,5,5,5-heptamethyl-3-vinyltrisiloxane (**XII**), 1,1,1,3,5,7,7,7-octamethyl-3,5-divinyltetrasiloxane (**XIII**), 1,1,1,3,5,7,9,9,9-nonamethyl-3,5,7-trivinylpentasiloxane (**XIII**)] and into decamethyltetrasiloxane [1,1,1,3,5,5,7,7,9,9,9-undecamethyl-3-vinylpentasiloxane (**XIV**)].

$$\mathbf{I} + \mathbf{III} \longrightarrow \text{Me}_{3} \text{SiO}(\text{MeVinSiO})_{n} \text{SiMe}_{3}, \qquad (5)$$

$$\mathbf{XI} - \mathbf{XIII}$$

$$n = 1 \quad (\mathbf{XI}), \quad 2 \quad (\mathbf{XII}), \quad 3 \quad (\mathbf{XIII}).$$

$$\mathbf{III} + \text{Me}_{3} \text{SiOSiMe}_{2} \text{OSiMe}_{2} \text{OSiMe}_{3}$$

$$\mathbf{X}$$

$$\longrightarrow \text{Me}_{3} \text{SiOSiMe}_{2} \text{OSiMe}_{2} \text{O}(\text{MeVinSiO}) \text{SiMe}_{3}. \quad (6)$$

Insertion products **XI–XIII** we also identified earlier in the reaction of MeVinSiCl₂ with DMSO and disiloxane **I** [1].

73 (9)

Ion	m/z $(I_{\rm rel}, \%)$					
	VIII	IX	XI	XII	XIII	XIV
$[M - Me]^+$	307 (60)	393 (33)	233 (100)	319 (52)	405 (47)	381 (12)
$[M - OSiMe_2Vin]^+$	221 (42)	307 (3)	147 (8)	233 (7)	319 (7)	295 (9)
$[M - \text{Me} - \text{Me}_{\Delta}\text{Si}]^+$	219 (80)	305 (36)	145 (4)	231 (25)	317 (19)	293 (86)
$[M - Vin - Me_{\underline{a}}Si]^{+}$	207 (100)	293 (100)	133 (17)	219 (100)	305 (85)	281 (100)
[Me ₃ SiOSiMeVin] ⁺		159 (55)	159 (3)	159 (1)	159 (77)	
[Me ₃ SiOSiMe ₂] ⁺	147 (2)	147 (41)	147 (7)	147 (2)	147 (29)	147 (12)
[Me ₃ SiOSiMeH] ⁺	133 (2)		133 (10)	133 (5)	133 (10)	
[Me ₂ VinSi] ⁺	85 (32)	85 (36)	85 (30)	85 (85)	85 (80)	_

73 (68)

59 (10)

Mass spectra of $Me_3Si(OSiMeVin)_n(OSiMe_2)_mOSiMe_3$ (VIII, IX, XI–XIV) [n = 1, m = 1 (VIII); n = 2, m = 1 (IX); n = 1, m = 0 (XII); n = 2, m = 0 (XII); n = 3, m = 0 (XIII); n = 1, m = 2 (XIV)]

The reaction of organyltrichlorosilanes RSiCl_3 (R = Me, Et) with DMSO in the presence of trisiloxane II (1:1:1 molar ratio) at 20°C gives no cycloorganyl-(trimethylsiloxy)siloxanes $[\operatorname{R}(\operatorname{Me}_3\operatorname{SiO})\operatorname{SiO}]_n$ that form in a high yield in the disiloxane I medium. The major products of the former reaction are cyclic oligoalkyl-chlorosiloxanes (RClSiO)_m (XV-XXI, m=3-6) whose yields reach 80%. Their formation can be explained in terms of cyclization of the intermediate alkyl chlorosilanones.

73 (62)

59 (7)

73 (59)

59 (12)

[Me₃Si]⁺

[Me₂SiH]⁺

$$m[RClSi=O] \longrightarrow (RClSiO)_m,$$
 (7)
 $XV-XXI$

R = Me, m = 3 (XV), 4 (XVI), 5 (XVII); R = Et, m = 3 (XVIII), 4 (XIX), 5 (XX), 6 (XXI).

EXPERIMENTAL

Gas chromatography–mass spectrometry was performed on an LKB-2091 GC–MS system at an ionizing voltage of 60 V, using an SE-54 capillary column, length 38 m. The oven temperature was raised at a rate of 16 deg/min to 270°C. Accelerating voltage 2 kV. The *m/z* values for chlorine-containing ions relate to ³⁵Cl. The intensity ratio for isotope peaks is consistent with calculation.

Dimethyl sulfoxide was kept over melted KOH, decanted, frozen, and distilled in a vacuum. Dichloro-(methyl)(vinyl)silane was purified by column rectification.

Reaction of dimethyl sulfoxide with dichloro-(methyl)(vinyl)silane in the presence of octamethyltrisiloxane (II). Dimethyl sulfoxide, 7.8 g, was added dropwise with cooling (0°C) to 14.1 g of dichloro(methyl)(vinyl)silane and 23.6 g of octamethyltrisiloxane, placed in a 50-ml flask equipped with a long Vigreux column. The mixture was heated to the boil. Therewith, 4.3 g (44%) of chloromethyl methyl sulfide distilled, bp $109-110^{\circ}$ C, $n_{\rm D}^{20}$ 1.4965 (bp $110-112^{\circ}$ C [3]). Found, %: C 25.25; H 5.24; Cl 36.94; S 32.85. C₂H₅ClS. Calculated, %: C 24.87; H 5.22; Cl 36.71; S 33.20. Along with chloromethyl methyl sulfide, dimethyl sulfide formed. Vacuum distillation of the residue gave a fraction [8.2 g (95%)] with bp $70-200^{\circ}$ C (6 mm). It was subjected to GC-MS analysis. The resulting data are presented in the table. The mass spectra of (MeVinSiO)_n (n = 3-6) have been reported in [4].

73 (100)

59 (32)

73 (80)

59 (23)

The reactions of Me₂SO with MeVinSiCl₂ in the presence of trisiloxane II (1:1:3 molar ratio) and with RSiCl3 were performed in a similar way. In the latter case, compounds XV-XXI were obtained.

Compound XV. Mass spectrum, m/z (I_{rel} , %): 267 (100) $[M - Me]^+$, 247 (11) $[M - Cl]^+$, 173 (10) $[M - Me - Me(Cl)SiO]^+$, 113 (16) $[MeSiCl_2]^+$, 93 (4) $[Me_2SiCl]^+$, 79 (12) $[M - Me - 2 Me(Cl)SiO]^+$.

Compound XVI. Mass spectrum, m/z (I_{rel} , %): 361 (100) $[M - Me]^+$, 341 (11) $[M - Cl]^+$, 267 (13) $[M - Me - Me(Cl)SiO]^+$, 173 (8) $[M - Me - 2Me(Cl)SiO]^+$, 113 (15) $[MeSiCl_2]^+$, 93 (24) $[Me_2SiCl]^+$.

Compound XVII. Mass spectrum, m/z (I_{rel} , %): 455 (65) $[M - Me]^+$, 435 (21) $[M - Cl]^+$, 361 (17) $[M - Me - Me(Cl)SiO]^+$, 267 (100) $[M - Me - 2Me(Cl)SiO]^+$, 113 (25) $[MeSiCl_2]^+$, 93 (74) $[Me_2SiCl]^+$.

Compound XVIII. Mass spectrum, m/z (I_{rel} , %): 295 (100) $[M - Et]^+$, 267 (34) $[M - 2Et + H]^+$, 187 (1)

 $[M - \text{Et} - \text{Et}(\text{Cl})\text{SiO}]^+$, 127 (2) $[\text{EtSiCl}_2]^+$, 121 (4) $[\text{Et}_2\text{SiCl}]^+$.

Compound XIX. Mass spectrum, m/z (I_{rel} , %): 403 (100) $[M - Et]^+$, 375 (34) $[M - 2Et + H]^+$, 295 (31) $[M - Et - Et(Cl)SiO]^+$, 187 (4) $[M - Et - 2Et(Cl)SiO]^+$, 127 (12) $[EtSiCl_2]^+$, 121 (14) $[Et_2SiCl]^+$.

Compound XX. Mass spectrum, m/z (I_{rel} , %): 511 (100) $[M - Et]^+$, 483 (14) $[M - 2 Et + H]^+$, 403 (11) $[M - Et - Et(Cl)SiO]^+$, 295 (4) $[M - Et - 2Et(Cl)SiO]^+$, 127 (11) $[EtSiCl_2]^+$, 121 (34) $[Et_2SiCl]^+$.

Compound XXI. Mass spectrum, m/z (I_{rel} , %): 619 (60) $[M - Et]^+$, 591 (14) $[M - 2Et + H]^+$, 511 (61) $[M - Et - Et(Cl)SiO]^+$, 403 (100) $[M - Et - Et(Cl)SiO]^+$

 $2\text{Et}(\text{Cl})\text{SiO}]^+$, 295 (75) $[M - \text{Et} - 3\text{Et}(\text{Cl})\text{SiO}]^+$, 127 (11) $[\text{Et}\text{SiCl}_2]^+$, 121 (33) $[\text{Et}_2\text{SiCl}]^+$.

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